

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|-----------|---|--|---|-------------------------|
| Applicant | : | NIINISTÖ et al. |) | Group Art Unit: Unknown |
| Appl. No. | : | Not yet assigned |) | |
| Filed | : | Herewith |) | |
| For | : | METHOD OF DEPOSITING RARE EARTH OXIDE THIN FILMS |) | |
| Examiner | : | Unknown |) | |

PRELIMINARY AMENDMENT

UNITED STATES PATENT AND TRADEMARK OFFICE
P.O. Box 2327
Arlington, VA 22202

Dear Sir:

Prior to examination on the merits, please amend the above-identified application as follows.

In the Claims:

Please replace claims 12 and 13 with the following replacement claims:

12. (Amended) A process according to claim 1, characterized in that the substrate is a silicon wafer or soda lime glass.

13. (Amended) A process according to claim 1, characterized in that the substrate is a compound semiconductor

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REMARKS

The specific changes to the claims are identified on the attached page that is captioned **"VERSION WITH MARKINGS TO SHOW CHANGES MADE."** Deletions are struck through.

Applicant submits that the present application is in condition for examination on the merits and respectfully requests the same.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: February 4, 2002

By: 

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the Claims:

Claims 12 and 13 have been amended as follows:

12. (Amended) A process according to claim 1 ~~or claim 5~~, characterized in that the substrate is a silicon wafer or soda lime glass.

13. (Amended) A process according to claim 1 ~~or claim 5~~, characterized in that the substrate is a compound semiconductor.

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